

PATENT NUMBER

M.S.	O.I.P.E.	PATENT DATE
SCANNED <u>Elu 1</u>	Q.A. <u>TM</u>	

O.I.P.E.

PATENT DATE

SCANNED Edu Q.A. Y/M

APPLICANTS	Keiji Emoto	100	2125	0
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APPLICANTS

TITLE

Pipe structure, alignment apparatus, electron beam lithography apparatus, exposure apparatus, exposure apparatus maintenance method, semiconductor device manufacturing method, and semiconductor manufacturing factory

ISSUING CLASSIFICATION									
ORIGINAL			CROSS REFERENCE(S)						
CLASS		SUBCLASS	CLASS	SUBCLASS (ONE SUBCLASS PER BLOCK)					
INTERNATIONAL CLASSIFICATION									

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<input type="checkbox"/> TERMINAL DISCLAIMER	DRAWINGS		CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed.	_____ (Assistant Examiner)		NOTICE OF ALLOWANCE MAILED _____	
<input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S Patent. No. _____ _____ _____	_____ (Primary Examiner)		ISSUE FEE Amount Due Date Paid	
<input type="checkbox"/> The terminal _____ months of this patent have been disclaimed.	_____ (Legal Instruments Examiner)		ISSUE BATCH NUMBER _____	

CLAIMS ALLOWED

Print Fig.

Print Claim for O.G.

(Assistant Examiner) (Date)

(Primary Examiner) (Date)

[illegible]

Date Paid

(Legal Instruments Examiner) (Date)

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